

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Narwankar et al.

Application No.: 10/772,893

Filed: February 4, 2004

For: TAILORING NITROGEN PROFILE
IN SILICON OXYNITRIDE USING
RAPID THERMAL ANNEALING WITH
AMMONIA UNDER ULTRA-LOW
PRESSURE

Examiner: Kelly M Stouffer

Art Unit: 1762

Confirmation No.: 5371

Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Dear Examiner:

This is in response to the Final Office Action mailed February 25, 2008 (and the Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 filed concurrently herewith). Applicants respectfully request the Examiner to enter this Amendment and consider the following remarks.

The Listing of Claims begins on page 2 of this paper.

Remarks/Arguments begin on page 12 of this paper.

I hereby certify that this correspondence is being deposited via
EFS Web on the date below:

May 16, 2008

Date of Deposit

/Justin K. Brask/

Justin K. Brask, Reg. #61,080